**PATENT** 

12105/ 12105/ Inter With RLC

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re: Ki-yeon Park et al. Serial No.: 10/828,596 Filed: April 21, 2004

Confirmation No.: 5520 Examiner: Ori Nadav Group Art Unit: 2811

For METHODS

METHODS OF FORMING METAL THIN FILMS, LANTHANUM OXIDE FILMS AND HIGH DIELECTRIC FILMS FOR SEMICONDUCTOR DEVICES USING

ATOMIC LAYER DEPOSITION

November 13, 2007

Mail Stop AF Commissioner for Patents P. O. Box 1450 Alexandria, VA 22313-1450

## AMENDMENT AFTER FINAL

Sir:

The present Amendment is being filed to address the issues raised in the final Office Action dated September 11, 2007.

It is not believed that an extension of time and/or additional fee(s)-including fees for net addition of claims-are required, beyond those that may otherwise be provided for in documents accompanying this paper. In the event, however, that an extension of time is necessary to allow consideration of this paper, such an extension is hereby petitioned under 37 C.F.R. §1.136(a). Any additional fees believed to be due in connection with this paper may be charged to our Deposit Account No. 50-0220.

Amendments to the Claims begin on page 2 of this paper.

Remarks begin on Page 12 of this paper.